IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of)
)
Zoran Krivokapic et al.) Group Art Unit: Unassigned
)
Application No.: Unassigned) Examiner: Unassigned
)
Filed: August 5, 2003)
)
Title: TRI-GATE FINFET)
WITH MESA ISOLATION)

INFORMATION DISCLOSURE STATEMENT UNDER 37 C.F.R. § 1.97(b)

U.S. Patent and Trademark Office 2011 South Clark Place Customer Window Crystal Plaza Two, Lobby, Room 1B03 Arlington, Virginia 22202

Sir:

Pursuant to 37 C.F.R. §§ 1.56 and 1.97(b), Applicant(s) bring to the attention of the Examiner the documents listed on the attached PTO 1449. This Information Disclosure Statement is being filed before the mailing date of a first Office Action in the above-referenced application. As such, no certification or fee is required. Copies of the listed documents are attached.

Applicant(s) respectfully request(s) that the Examiner consider the listed documents and indicate that they were considered by making appropriate notations on the attached form.

attention is directed to the foregoing application(s) in compliance with § 2001.06(b) of the

Manual of Patent Examining Procedure. By identifying the copending application(s), the

assignee and/or applicant of the application(s) do not waive confidentiality of the application(s).

If any copending application(s) is/are cited on the attached PTO 1449, the Examiner's

Accordingly, the U.S. Patent and Trademark Office is requested to maintain the confidentiality

of the copending application(s) under 35 U.S.C. § 122.

This submission does not represent that a search has been made and does not constitute

an admission that each or all of the listed documents are material or constitute "prior art." If the

Examiner applies any of the documents as prior art against any claim in the application and

Applicant(s) determine(s) that the cited document(s) do not constitute "prior art" under United

States law, Applicant(s) reserve(s) the right to present to the Office the relevant facts and law

regarding the appropriate status of such documents.

Applicant(s) further reserve(s) the right to take appropriate action to establish the

patentability of the disclosed invention over the listed documents, should one or more of the

documents be applied against the claims of the present application.

If there is any fee due in connection with the filing of this Statement, please charge the fee to our Deposit Account No. 50-1070.

Respectfully submitted,

HARRITY & SNYDER, L.L.P.

By: Tony M. Cole

Reg. No. 43,417

11240 Waples Mill Road Suite 300 Fairfax, Virginia 22030 (571) 432-0800

Customer Number: 26615

Date: August 5, 2003

INFORMATION DISCLOSURE CITATION

Customer Number: 26615

ATTORNEY'S DKT NO. H1164	Application No. Unassigned
APPLICANT(S) Zoran Krivokapic et al.	
FILING DATE August 5, 2003	GROUP Unassigned

	PTO-1449										
U.S. PATENT DOCUMENTS											
EXAMINER'S INITIALS	PATENT NO.	DATE	NAME		CLASS	SUBCLASS	FILI DA				
FOREIGN PATENT DOCUMENTS											
EXAMINER'S INITIALS	DATENT NO.	DATE	COUNTRY	ev /	CLASS	SUBCLASS	Translation				
INITIALS PATENT NO. DATE	DATE	COUNTRY		CLASS	GOBOLAGO	Yes	No				
·											
	OTHER DOCU	MENTS (I	Including Author, Titl	le, Date, Pertine	nt Page	es, Etc.)					
Digh Hisamoto et al., "FinFET-A Self-Aligned Double-Gate MOSFET Scalable to 20 nm," IEEE Transactions on Electron Devices, Vol. 47, No. 12, December 2000, pages 2320- 2325.											
Yang-Kyu Choi et al., "Sub-20nm CMOS FinFET Technologies," 2001 IEEE, IEDM, pages 421-424.											
	Xuejue Huang et al., "Sub-50 nm P-Channel FinFET," IEEE Transactions on Electron Devices, Vol. 48, No. 5, May 2001, pages 880-886.										
	Xuejue Huang et al., "Sub 50-nm FinFET: PMOS," 1999 IEEE, IEDM, pages 67-70.										
Yang-Kyu Choi et al., "Nanoscale CMOS Spacer FinFET for the Terabit Era," IEEE Electron Device Letters, Vol. 23, No. 1, January 2002, pages 25-27.											
EXAMINER	DATE CONSIDERED										

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant(s).